

The Examiner objected to claim 11 because of informalities. Claim 11 has been amended to add a comma between “Mo” and “Cr” as suggested by the Examiner.

The Examiner rejected claims 1, 2, and 11 under 35 USC § 102(a) as being anticipated by Havemann et al. (US Patent No. 5,891,804). This rejection is respectfully traversed.

Claim 1 is allowable at least for the reason that claim 1 recites a combination of elements including etching a portion of the substrate to form a groove using the photoresist pattern as a mask. None of the cited references teaches or suggests each and every element of the claims.

Column 3, lines 29-38 of Havemann et al. recites “FIG 1B show the structure after the photoresist has been patterned and the underlying layers etched down to the substrate 10.”

Therefore, Havemann et al. do not disclose etching a portion of the *substrate*. On page 2 of the Office Action, the Examiner refers to the substrate as layers 44/42/40/30/10. Applicant submits that layers 44/40/42/30 are the underlying layers in FIGs 2A-2E and 3A-3G of Havemann et al. and are not a substrate. Applicant submits that claim 1 is allowable over the cited reference. Applicant respectfully requests that the rejection under 35 USC 102(a) be withdrawn.

Moreover, claims 2 and 11 are allowable by virtue of their dependence on claim 1, which is believed to be allowable.

The Examiner rejected claims 4, 5, 7, 8, and 10 under 35 USC 103(a) as being unpatentable over Havemann et al. as applied to claims 1, 2, and 11 above, and further in view of Senda et al. (US Patent No. 5,364,459). The Examiner rejected claims 3, 6, and 9 under 35 USC 103(a) as being unpatentable over Havemann et al. and Senda et al. as applied to claims 1, 2, 4, 5, 7, 8, 10, and 11 above, and further in view of Charneski et al. (US Patent

No. 6,284,652). The Examiner rejected claims 12 and 13 under 35 USC 103(a) as being unpatentable over Havemann et al. and Senda et al. as applied to claims 1, 2, 4, 5, 7, 8, 10, and 11 above, and further in view of (JP 05-265040). These rejections are respectfully traversed.

On page 3 of the Office Action the Examiner acknowledges that Havemann et al. does not disclose Ag and Au and the material for the reductant. The Examiner cites Senda et al. to cure the deficiencies in Havemann et al. On page 4 of the Office Action, the Examiner acknowledges that Havemann et al. and Senda et al. do not disclose the mixed solution for the electroless plating. The Examiner cites Charneski et al. to cure the deficiencies in Havemann et al. and Senda et al. As discussed above, independent claim 1 recites a combination of elements including etching a portion of the substrate to form a groove using the photoresist pattern as a mask. None of the cited references, singly or in combination, teaches or suggests all of the elements of the claims.

Senda et al. and Charneski et al. fail to cure the deficiencies of Havemann et al. since the dependent claims incorporate all of the elements of the independent claims. Applicant submits that claims 3-10, 12, and 13 are allowable by virtue of their dependence on claim 1, which is believed to be allowable. Accordingly, for at least these reasons, Applicant respectfully requests that the Examiner withdraw the rejection of claims 3-10, 12, and 13 as based on any combination of Havemann et al., Senda et al. and Charneski et al.

In view of the foregoing, Applicant respectfully requests that the application be reconsidered, that claims 1-13 be allowed, and the application pass to issue.

If the Examiner deems that a telephone conference would further the prosecution of this application, the Examiner is invited to call the undersigned attorney at (202) 624-1200.

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under

37 C.F.R. §1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911. Please credit any overpayment to deposit Account No. 50-0911.

Respectfully submitted,

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**MARKED-UP VERSION OF AMENDED CLAIMS**

Claim 11. (Amended) The method of claim 1, wherein the second metal is one of Pd, Pt, Au, Cu, Mo<sub>x</sub> Cr, Ti, Ni, W and Co.